

Docket No.

0160-0193-0 PCT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Hiroshi IKEDA, ET AL.

GAU:

1754

SERIAL NO: 09/463,961

EXAMINER: VANOY, T.

FILED:

MAY 25, 2000

FOR:

METHOD AND APPARATUS FOR PROCESSING EXHAUST GAS OF SEMICONDUCTOR FABRICATION

REQUEST FOR EXTENSION OF TIME **UNDER 37 C.F.R. 1.136**

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

RECEIVED

It is hereby requested that a one month extension of time be granted to OCTOBER 19, 2001 fcf CT 0.3 2001

	• •	ě	, 661	A A VAAI
	filing a response to the Official Action dated:	JUNE 19, 2001	TO	# * * * * * * * * * *
	responding to the requirements in the Notice of	onding to the requirements in the Notice of Allowability dated:		7700
	filing the Formal Drawings. The Issue Fee due		has been timely filed.	٠
	responding to the Notice to File Missing Parts of Application dated:			
	filing a Notice of Appeal. A timely response to the final rejection, due			has been filed.
	filing an Appeal Brief. A Notice of Appeal was	s filed on:		
П	Applicant claims small entity status See 37 C	FR 1.27 Therefore the	fee amount shown helo	w is reduced by one-half

The required fee of \$110.00 is enclosed herewith by check and any further charges may be made against the Attorney of Record's Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,

MAIER & NEUSTADT, P.C.

22850

Tel. (703) 413-3000 Fax. (703) 413-2220 (OSMMN 11/98)

Norman F. Oblon

Registration No. 24,618

Corwin P. Umbach, Ph.D.

Registration No. 40,211

10/03/2001 MBERHE

00000039 09463961

01 FC:115

110.00 CP